

Helium and Nitrogen Purifiers

- Point-of-use purification to low ppm levels
- CE-compliant
- Simple maintenance
- Self-regulated 24 VDC power



Description and Operating Principle

Carrier gas purity is essential in any application requiring extreme sensitivity. Impurities limit detector sensitivity and can even destroy capillary columns. The Valco HP2 (helium purifier) provides "point-of-use" purification of helium or other noble gases, such as Ar, Ne, Kr, and Xe, to sub-ppm levels of reactive gaseous impurities. The NP2 (nitrogen purifier) is similar, purifying nitrogen to sub-ppm levels of gaseous impurities.

The purification substrate in Valco gas purifiers is a nonevaporable gettering alloy. This stable alloy is contained in a welded assembly, so the purifiers can be used safely in industrial applications with minimal precautions. The getter is activated by heating, which eliminates the oxide film on the particle surface and allows helium to diffuse into the bulk of the getter particles. This leaves the surface free from the passivating oxide layers and available for sorption. Activation must be performed under a vacuum or inert gas (He, Ar, Kr, or Xe) atmosphere. The helium and nitrogen purifiers feature a self-regulating design which eliminates the possibility of thermal runaway and maintains the getter material at the optimum temperature.

Specifications

	Helium Purifier (HP2)	Nitrogen Purifier (NP2)		
Gases purified	He, Ne, Ar, Kr, Xe, Rn	Ar, Kr, Xe, Rn He, Ne, Ar, Kr, Xe, Rn, N ₂		
Max. operating pressure	1000 psig	1000 psig		
Max. operating temperature	400°C	400°C		
Max. flow rate	1 liter/min	1 liter/min		
Impurities removed	Outlet impurities less than 10 ppb H_2O , H_2 , O_2 , N_2 , NO , NH_3 , CO , and CO_2 , based on 100 ppm total inlet impurities. Other impurities removed include CF_4 , CCI_4 , SiH_4 , and hydrocarbons such as CH_4	Outlet impurities less than 10 ppb H_2O , H_2 , O_2 , NO , NH_3 , CO , and CO_2 , based on 100 ppm total inlet impurities. Other impurities removed include CF_4 , CCI_4 , SiH_4 , and hydrocarbons other than CH_4		
Impurities not removed	He, Ne, Ar, Kr, Xe, and Rn	He, Ne, Ar, Kr, Xe, Rn, $\mathrm{CH_4}$, and $\mathrm{N_2}$		

Miniature Gas Purifiers

Virtually all commercial gas chromatographs contain certain components which, while adequate for flame ionization and thermal conductivity detectors, are unsuitable for low ppb universal analyses. For



example, unheated molecular sieve traps are certain to contaminate the carrier gas with CO_2 and H_2O .

The Valco Miniature Helium Purifier (HPM) and Miniature Nitrogen Purifier (NPM) are designed to address this situation, providing "point-of-use" carrier gas purification to sub-ppm levels of gaseous impurities. When installed in a gas chromatograph's flow path immediately upstream of the injector, the HPM/NPM will remove any contaminants introduced by flow controllers, elastomeric tube seals, pressure regulators, crude traps, or other system components that are not completely clean and leak-tight.

Specifications

Helium Purifier (HPM) Nitrogen Purifier (NPM) Gases purified He, Ne, Ar, Kr, Xe, Rn He, Ne, Ar, Kr, Xe, Rn, N₂ Max. operating pressure 200 psig 200 psig Max. operating temperature 400°C 400°C Max. flow rate 30 cc/min 30 cc/min Impurities removed Outlet impurities less than 10 ppb Outlet impurities less than 10 ppb H₂O, H₂, O₂, N₂, NO, NH₃, CO, H₂O, H₂, O₂, NO, NH₃, CO, and and CO2, based on 100 ppm total CO₂, based on 100 ppm total inlet inlet impurities. Other impurities impurities. Other impurities removed removed include CF₄, CCI₄, SiH₄, include CF₄, CCI₄, SiH₄, and and hydrocarbons such as CH₄ hydrocarbons other than CH₄ Impurities not removed He, Ne, Ar, Kr, Xe, Rn, CH₄, and N₂ He, Ne, Ar, Kr, Xe, and Rn

Ordering Information

Description Product numbers

Standard helium and nitrogen purifiers

 Helium
 Nitrogen

 110 VAC
 HP2
 NP2

 220 VAC
 HP2-220
 NP2-220

 Replacement getter assembly
 I-23572
 I-23572NP2

Miniature helium and nitrogen purifiers

 Helium
 Nitrogen

 110 VAC
 HPM
 NPM

 220 VAC
 HPM-220
 NPM-220



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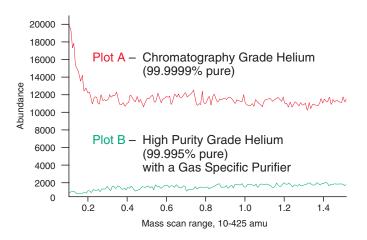
Gas Specific Purifiers and Contaminant Traps

- Reduce gas impurities from high PPM to low PPB levels
- Decrease baseline noise and increase GC/MS sensitivity
- Replace three traps with one purifier



Description

Several types of contaminants are detrimental to GC performance – notably moisture, hydrocarbons, and oxygen. VICI Metronics gas-specific purifier modules are designed to be placed in-line with the GC carrier or detector gas supply to remove these contaminants from the analytical gases prior to entering the GC. The modules dramatically reduce contaminant levels and absorb a greater variety of contaminants than other products.



Performance is optimized by a multiple bed format. Each bed functions at a lower contaminant concentration, resulting in a series of contaminant concentration gradients across the length of the module. Advanced materials and design features guarantee that the modules will produce gases that are at least a factor of ten higher than a 99.9999% "chromatography grade" cylinder of gas when the purifier is supplied by a 99.995% cylinder. The cost difference between the two grades of gas will pay for the cost of the purifier several times over during its operating life.

Our successive bed format achieves the highest purity gas commercially available

Two very high capacity hydrocarbon and moisture sorbents at the inlet for effective contaminant removal

Unique proprietary broad spectrum sorbent material for multiple contaminant removal

Two oxygen scavenging materials for both high capacity and high efficiency O₂ removal

Multiple bed format to allow several step reduction in contaminants

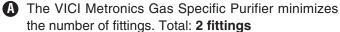
Removal of H₂O, O₂, halocarbons, hydrocarbons, CO, CO₂, H₂, and sulfur containing compounds with a single purifier

Very high efficiency sorbents at the outlet for trace contaminant removal



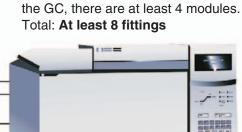
Fittings: the Fewer the Better

Every connection in your gas delivery system has the potential for leaks; the more fittings you have, the greater the potential. In the illustration below, several gas purification options are depicted:



B The "Manifold System" has two compression fittings for the system and one organic O-ring seal for each cartridge. Total: At least 5 fittings

G A typical "Contaminant Trap" configuration has several components. Before the gas supply even enters the GC, there are at least 4 modules.



Specifications

Length	52.3 cm (21")
Diameter	3.8 cm (1.5")
Maximum inlet pressure	6895 kPa (1000 psi)
Maximum recommended flow	500 ml/min

Selection Guide and Ordering Information

Product Description	Product no.	Fitting	PPB at outlet, based on 50 PPM nominal inlet concentration level					
			CO	CO ₂	02	H ₂ 0	Sulfur compounds	NMHC*
Helium purifier	P-100-1 P-100-2	1/8" 1/4"	<1	<1	<1	<1	<1	<3
Hydrogen purifier	P-200-1 P-200-2	1/8" 1/4"	<1	<1	<1	<1	<1	<3
Nitrogen purifier	P-300-1 P-300-2	1/8" 1/4"	<1	<1	<1	<1	<1	<3
Nitrogen purifier for LC/MS apps	P-310-1 P-310-2	1/8" 1/4"				<25	<25	<25
Purifier for nitrogen generators	P-350-1 P-350-2	1/8" 1/4"				<25	<25	<25
Air purifier	P-400-1 P-400-2	1/8" 1/4"				<1		<3
Moisture trap	T-100-1 T-100-2	1/8" 1/4"				<1		
Hydrocarbon trap	T-200-1 T-200-2	1/8" 1/4"						<3
Oxygen trap	T-300-1 T-300-2	1/8" 1/4"			<1	<1		
Sulfur trap	T-400-1	1/8"				<1	<1	
Methane purifier	P-500-1	1/8"	<1	<1	<1	<1	<1	<3
Carbon dioxide	P-600-1 P-600-2	1/8" 1/4"	<1		<1	<1	<1	<3

*NMHC = non-methane hydrocarbons



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